DESCRIPTION

~~DRESSING DEVICE FOR POLISHING-USE FOAMED URETHANE PAD~~

TECHNICAL FIELD

[0001]

The present invention relates to a dressing apparatus for dressing a urethane foam pad for use in polishing a wafer.

BACKGROUND ART

[0002]

In polishing of wafers, a urethane foam pad has been used to improve flatness of the surfaces of the wafers. The urethane foam pad for use in polishing is subjected to initial dressing for starting up before the use, followed by periodically batch-to-batch dressing at intervals of polishing batches. Such periodical dressing of the urethane foam pad enables setting of the urethane foam pad, thereby keeping flatness quality of wafers after polishing.

[0003]

A dressing apparatus having diamond abrasive grains is generally used for dressing a urethane foam pad. The dressing apparatus is configured to dress a urethane foam pad by bringing one-grit-size diamond abrasive grains which are regularly or irregularly arranged on a support into sliding contact with the urethane foam pad.

CITATION LIST

PATENT LITERATURE

[0004]

Patent Document 1: Japanese Unexamined Patent publication

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APPARATUS FOR DRESSING URETHANE FOAM PAD FOR USE IN POLISHING

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